

	L #	Hits	Search Text	DBs	Time Stamp
1	L1	276	(427/539).CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2002/03/21 13:29
2	L2	129187	tantalum Ta Titanium Ti zirconium Zr barium Ba strontium Sr)adj(oxide dioxide pentoxide	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2002/03/21 13:34
3	L3	223799	tantalum Ta Titanium Ti zirconium Zr barium Ba strontium Sr)with(oxide dioxide pentoxide	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2002/03/21 13:36
4	L4	97031	"TiO.sub.2" TiO2 "Ta.sub.2 O.sub.5" Ta2O5 "ZrO.sub.2" ZrO2 BaO BaO2 "BaO.sub.2" SrO SrO2 "SrO.sub.2"	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2002/03/21 13:41
5	L5	29	1 and (2 or 4)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2002/03/21 13:42

09/617,254
03/21/2002, EAST Version: 1.03.0002

2

	L #	Hits	Search Text	DBs	Time Stamp
6	L5	29	1 and (2 or 4)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2002/03/21 13:45
7	L7	2040	(427/553-559).CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2002/03/21 13:45
8	L8	232	7 and (2 or 4)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2002/03/21 13:46
9	L9	141	8 and (UV or ultraviolet or ultra violet)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2002/03/21 13:47

L10 (→) Circum or Titania
 L11 31 (1 and 10) not (5 or 6)
 Stupid computer (or programmer) doesn't know
 the difference between a circle & a planet

LS

3

	Document ID	Issue Date	Title	Current OR	Inventor
1	US 200100543 88 A1	20011227 X	Single-substrate-film-forming method and single-substrate-heat-processing apparatus	118/725	Qian, Shao Shou
2	US 6333065 B1	20011225 Cd. 7/17/98 K	Process for the production of an organic electroluminescent device	427/66	Arai, Michio et al.
3	<div style="position: absolute; top: 0; left: 0;"> (AD) sub- polymer, oxides... (D) the ceramic mat... ZrO_2 5/16/97 P11 → 4/11/97 Fig 1 - 10b </div> US 6300641 B1	20011009	Process for modifying surfaces of materials, and materials having surfaces modified thereby	250/492.2 1	Koh, Seok Keun et al.
4	US 6270860 B1	20010807 4/25/95	Method of making push button switch covering with protective coating	427/536	Nakata, Toshihiro et al.

	Document ID	Issue Date	Title	Current OR	Inventor
5	US 6156114 A	20001205	Treatment of deagglomerated particles with plasma-activated species	106/400	Bell, Timothy Allan et al.
6	US 6103315 A	20000815 4/13/98	Method for modifying the surface of a thermal barrier coating by plasma-heating	427/454	Gray, Dennis Michael et al.

Full
data
x

Ab5 - plasma spray

this plasma heat → re-melt

	Document ID	Issue Date	Title	Current OR	Inventor
7	US 6086726 A	20000711 5/19/98 100-1000	Method of modifying a surface	204/192.1	Renk, Timothy J. et al.
Col. 8, l 26-31 (B) the anti reflect coating... ... TiO ₂ , ZnO ₂ , H ₂ O ₅	Col. 8, l 59-60 may prefer not to use anti Ref. Layer	8 US 6051310 A 20000418 905 P. 1/1/96	Ophthalmi c lens made of organic glass with a shockproo f intermedi ate layer, and method for making same	428/336	Cano, Jean Paul et al.

	Document ID	Issue Date	Title	Current OR	Inventor
9	US 6033493 A	20000307 <i>7/10/97</i> <i>PCR Pub. 4/1/96</i>	Process for coating a passivated metal or alloy substrate with an oxide layer, and fuel assembly cladding and guide tubes and spacer grid coated with an oxide layer	148/276	Hertz, Dominique et al.
10	US 5972436 A	19991026 <i>7/24/97</i>	CVD process for coating the inside of hollow bodies	427/535	Walther, Marten
11	US 5958524 A	19990928 <i>4/17/95</i>	Process for the surface treatment of articles comprising at least one plastic material	427/533	Dehennau, Claude et al.
12	US 5945175 A	19990831 <i>4/1/96</i>	Durable hydrophilic coating for a porous hydrophobic polymer substrate	427/534	Yahiaoui, Ali et al.

(B) It has, for ex. - 7/10/97
full - cite with
oxidizes to metal with
coat 3 w/ ZrO₂

(D) A. Calandrelli
??
11 pdr of TiO₂
✓
cont → 4/17/95

	Document ID	Issue Date	Title	Current OR	Inventor
13	US 5919326 A <i>AN-578, 5/1/95</i>	19990706	Method for the production of a fuel hose	156/244.13	Yokoe, Katsuhiko et al.
14	US 5853819 A	19981229	Imaging element comprising an electrically conductive layer formed by a glow discharge process	427/537	Lelental, Mark et al.
15	US 5780118 A <i>Coat on paper w/ TiO₂ filler</i>	19980714 <i>7/1/96</i>	Method for increasing hydrophilicity of transparencies used as recording media in a thermal ink jet printer	427/508	Tracy, Mark D. et al.
16	US 5780115 A <i>(B) In porous medium... Ta₂O₅ dielectric (B) Hydrothermal synthesis... T=200-500°C; P=1-50 bar</i>	19980714 <i>2/2/97</i>	Methods for fabricating electrode structures including oxygen and nitrogen plasma treatments	427/539	Park, In-sung et al.
17	US 5718957 A	19980217	Fuel hose	428/36.91	Yokoe, Katsuhiko et al.

	Document ID	Issue Date	Title	Current OR	Inventor
18	US 5618388 A <i>dup Ta /ox dig/ dup Si/</i>	✓ 19970408	Geometries and configurations for magnetron sputtering apparatus	204/192.12	Seeser, James W. et al.
19	US 5562952 A	19961008	Plasma-CVD method and apparatus	427/534	Nakahigashi, Takahiro et al.
20	Abs ITO - O^{+} <i>chaser deposit</i> US 5538905 A <i>Fig 3D $\downarrow O_2$</i>	19960723	Method for forming a transparent conductive ITO film	438/609	Nishioka, Yukiya et al.

100% protection
 $Col 4, 246 \quad O \equiv 10^{16} - 10^{17} \text{ cm}^{-2}$

	Document ID	Issue Date	Title	Current OR	Inventor
<p>(D) $15\text{e} = (\text{H}_2\text{O}_3)$ stat. ZrO_2</p> <p>102 = 15e</p> <p>21</p>	US 5468326 A	19951121	Apparatus for polishing a diamond or carbon nitride film by reaction with oxygen transported to the film through a superionic conductor in contact with the film	156/345	Cuomo, Jerome J. et al.
<p>22</p>	US 5466424 A	19951114	Corona discharge surface treating method	422/186.05	Kusano, Yukihiro et al.
<p>(D) To the same process - Ba oxide</p> <p>(B) table with TiO_2</p> <p>2</p>	US 5397597 A	19950314	Optical recording medium and method of manufacturing the same	427/255.6	Soga, Mamoru et al.

cd. 4, 1 28-36
 air + H_2 , O_2
 0.2-16 - sub 3

(B) IT is possible... inorganic oxide layer $\Rightarrow \text{TiO}_2$

B = metal oxide film

Ex 1 opt. red layer (2) ($\text{TeO}_2 + \text{Te}$) dep. sub (1)
 then apply another sub (1) w/ UV-address, then
 O-plasma treat in UV stepper

Ex 5 } sub 11 / (TeO_2 / Te) / SiO_2
 6 } TiO_2 the O-plasma treat

	Document ID	Issue Date	Title	Current OR	Inventor
24	US 5328524 A <i>plasma etching metal</i>	19940712	Process for the surface oxidation of a part composed of passivatable metal, and fuel assembly elements composed of metal alloy covered with a protective oxide layer	148/241	Hertz, Dominique
25	US 5295220 A <i>Ab... TiO₂ film via plasma CVD</i> <i>(D) Prod. of waveguide of TiO₂...</i> <i>protect - C - plasma</i>	19940315	Process for the production of a thin film optical waveguide of TiO ₂ sub.2	385/142	Heming, Martin et al.
26	US 5268208 A <i>(D) H₂ internal plasma metal under = TiO₂</i>	19931207	Plasma enhanced chemical vapor deposition of oxide film stack	427/576	Krisko, Annette J. et al.
27	US 4816292 A	19890328	Method of preparing hexagonal ferrite element	427/539	Machida, Hajime

(D) this treatment can be pref... ZnO₂... TiO₂...

	Document ID	Issue Date	Title	Current OR	Inventor
28	US 4128426 A	19781205	Process for subbing photograp hic hydrophob ic films	427/536	Ohta, Hideyasu et al.
29	JP 60110379 A	19850615	METHOD FOR COATING POLYPROPY LENE RESIN PARTS		YUUSAI, KATSUICHI